

Materials List for:

A Standard and Reliable Method to Fabricate Two-Dimensional Nanoelectronics

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Materials

Name	Company	Catalog Number	Comments
E-gun Evaporator	AST	PEVA 600I	
Au slug, 99.99%	Well-Being Enterprise Co	N/A	
Ti slug, 99.99%	Well-Being Enterprise Co	N/A	
E-beam Lithography System	Elionix	ELS7500-EX	
Cold Wall CVD System	Sulfur Science	SCW600S	
C-plane Sapphire substrate	Summit-Tech	X171999	(0001) ± 0.2 ° one side polished
100 nm SiO ₂ /Si			Fabricated in NDL
Ammonia Solution	BASF	Ammonia Solution 28% Selectipur	
Molybdenum (Mo), 99.95%	Summit-Tech	N/A	
Tungsten (W), 99.95%	Summit-Tech	N/A	
Sulfur (S), 99.5%	Sigma-Aldrich	13803	
Polymethyl Methacrylate (PMMA)	Microchem	8110788	Use for transfer process
Spin Coater	Laurell	WS 400B 6NPP LITE	
Acetone	BASF	Acetone EL Selectipur	
Isopropanol (IPA)	BASF	2-Propanol UPS	
Photo Resist for EBL	TOK	TDUR-P-015	
Plasma Cleaner	Harrick Plasma	PDC-32G	Oxygen plasma